Title (en)
METHOD FOR FORMING POROUSCATALYTIC MATERIAL IN MICROCAVITY OR MICROPASSAGE BY MECHANOCHEMICAL POLISHING

Title (de)
VERFAHREN ZUR FORMUNG EINES PORÖSEN KATALYTISCHEN MATERIALS IN EINEM MIKROHOHLRAUM ODER EINEM MIKRODURCHGANG DURCH MECHANOCHEMISCHES POLIEREN

Title (fr)
PROCÉDÉ DE FORMATION DE MATÉRIAU CATALYSEUR POREUX DANS UNE MICROCAVITÉ OU UN MICROPASSAGE PAR POLISSAGE MÉCANO-CHIMIQUE

Publication
EP 2263253 A2 20101222 (FR)

Application
EP 09734307 A 20090330

Priority
• FR 2009000369 W 20090330
• FR 0801921 A 20080408

Abstract (en)
[origin: WO2009130416A2] A surface of a substrate (2) comprising microcavities (1) leading out of the substrate is placed in contact with an aqueous solution comprising a plurality of suspended particles (4) and a fabric (3). Perpendicular pressure is applied the expanse of the substrate (2) between the fabric (3) and the surface of the substrate (2), and relative movement of the fabric (3) and the surface is applied to the expanse of the substrate. At least one particle (4) is thus fed into each microcavity (1), therein forming a porous material that is a catalyst material for nanothread or nanotube growth.

IPC 8 full level
H01L 21/316 (2006.01); C01B 31/02 (2006.01); H01L 21/762 (2006.01); H01L 21/768 (2006.01)

CPC (source: EP US)
H01L 21/02126 (2013.01 - EP US); H01L 21/02203 (2013.01 - EP US); H01L 21/02282 (2013.01 - EP US); H01L 21/31695 (2016.02 - US); H01L 21/76224 (2013.01 - EP US); H01L 21/7682 (2013.01 - EP US); H01L 21/76877 (2013.01 - EP US); H01L 23/53276 (2013.01 - EP US); H01L 21/764 (2013.01 - EP US); H01L 2221/1094 (2013.01 - EP US); H01L 2924/0002 (2013.01 - EP US)

Citation (search report)
See references of WO 2009130416A2

Designated contracting state (EPC)
AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO SE SI SK TR

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DOCDB simple family (publication)
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